

# Radio-Frequency Graphene Field-Effect Transistors Based on Millimeter-Scale Graphene Domain

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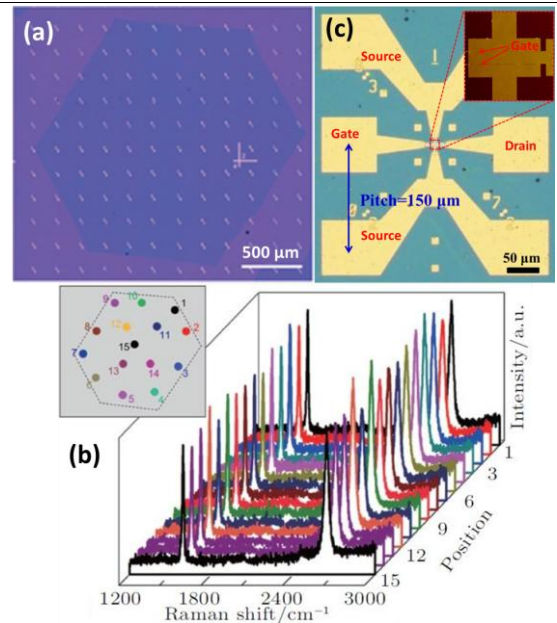
## Abstract

Graphene is a promising candidate in radio-frequency (RF) applications due to its ultrahigh carrier mobility [1], and tolerance to large current density [2]. Several advanced techniques have been exploited in fabricating graphene field-effect transistor (FET) involving reduction of access resistance, gate capacitance, output conductance [3], contact resistance [4] and enhancement of insulating layer quality [5], seeking for high cut-off frequency ( $f_T$ ) and maximum oscillation frequency ( $f_{max}$ ). Here, we present high-performance top-gated RF FETs using a millimeter-scale graphene domain with a conventional fabrication process. A maximum  $f_T$  of 178 GHz and a peak  $f_{max}$  of 35 GHz are achieved in the graphene-domain-based FET with a gate length of 50 nm and 150 nm, respectively. This work shows that the millimeter-scale single graphene domain has great potential in RF devices and circuits.

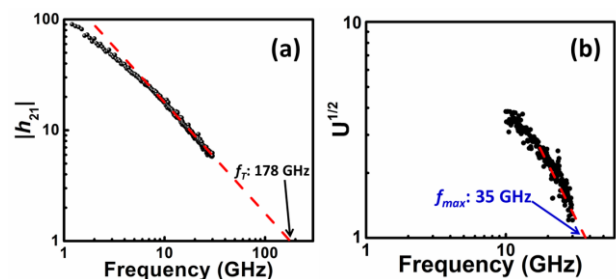
## References

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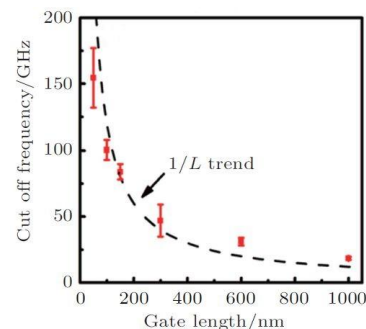
## Figures



**Figure 1:** (a) Optical image of an individual graphene domain; (b) Optical image of a GFET with an AFM zoom-in picture at active region; (c) Raman spectra of the graphene domain.



**Figure 2:** Plots of de-embedded current gain of a 50-nm-gate GFET (a) and Mason unilateral power gain of a 150-nm-gate GFET (b).



**Figure 3:** Variations of peak  $f_T$  with gate length ( $L$ ) obtained from 30 devices. The dashed line indicates their  $1/L$  dependence